## REMARKS

We are in receipt of the Office Action dated August 6, 2003, and the above amendment and following remarks are made in light thereof.

Claims 1-24 are pending in the application, with Claims 25-31 having been withdrawn pursuant to an election and now canceled.

Pursuant to the Office Action, Claims 1-24 stand rejected under 35 U.S.C. 102(b) as being anticipated by Japanese laid open applications 08-254713 (herein "Fukuda").

By the foregoing amendment Claims 1, 13 and 19 have been amended to require the channel formation region to be formed in the crystalline semiconductor film. Claim 7 requires a gate insulating film comprising at least a single layer on the channel formation region.

In contrast, <u>Fukuda</u> discloses that the source, drain and channel regions are formed on the gate insulating layer. Accordingly, applicant believes that each of the independent claims 1, 7, 13 and 19 are not anticipated by <u>Fukuda</u>. The remaining claims are dependent from the independent 1, 7, 13 and 19 and are not anticipated by <u>Fukuda</u> for the same reason.

In view of the foregoing, applicant respectfully submits that the application is now in condition for allowance, and an early Office Action in this regard is earnestly solicited.

Respectfully submitted,

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Stephen B. Heller Attorney of Record Registration No.: 30,181

COOK, ALEX, McFARRON, MANZO,

CUMMINGS & MEHLER, LTD. 200 West Adams Street, Suite 2850

Chicago, Illinois 60606

(312) 236-8500